

ANWENDUNG
DER
KONTROLL-
THEORIE
AN DER
MIKRO-
LITHOGRAPHIE

G. Crosta

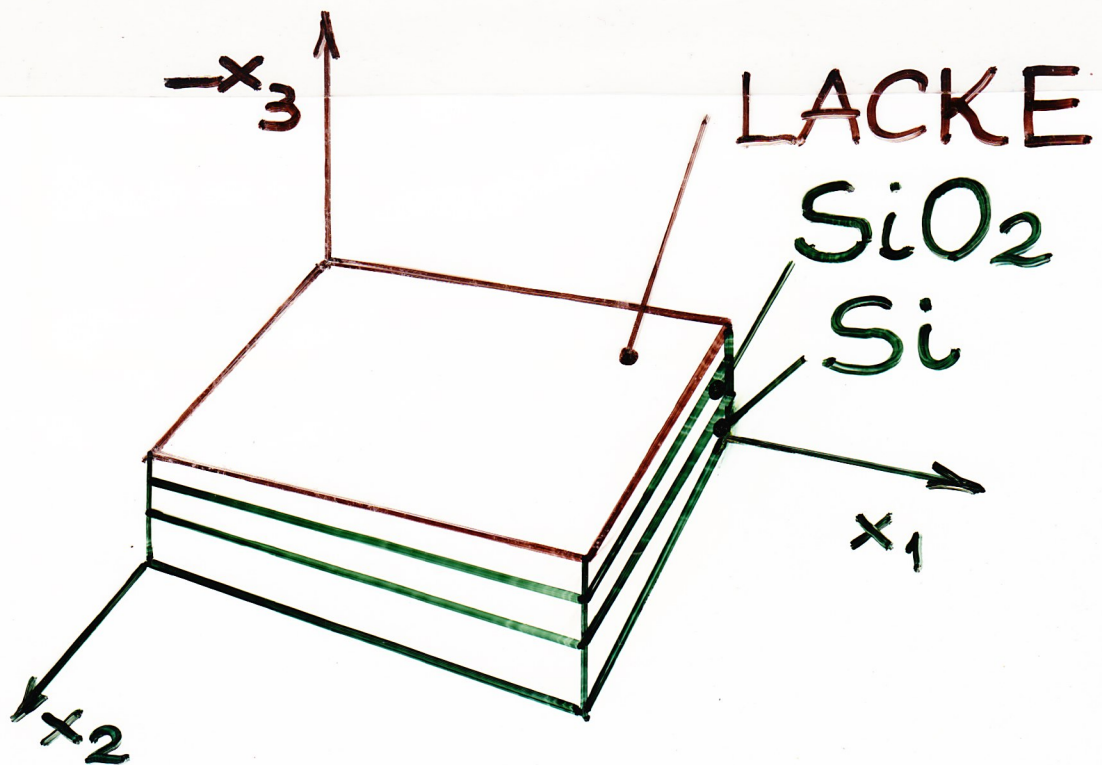
DG 81-BREMEN

10. Juni

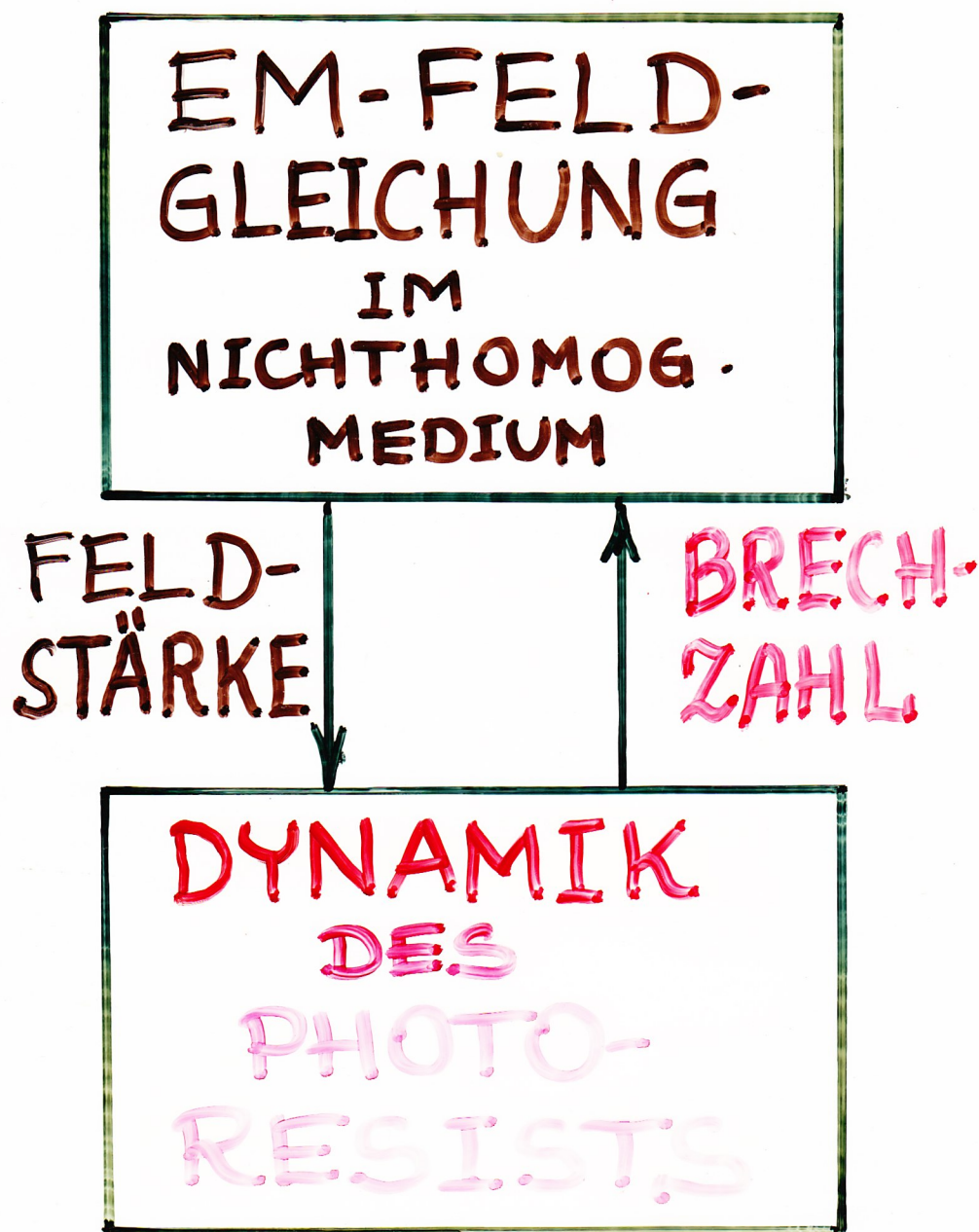
LICHTQUELLE BINÄRMASKE

OPTISCHES
Fourier Optik & MÜF
SYSTEM

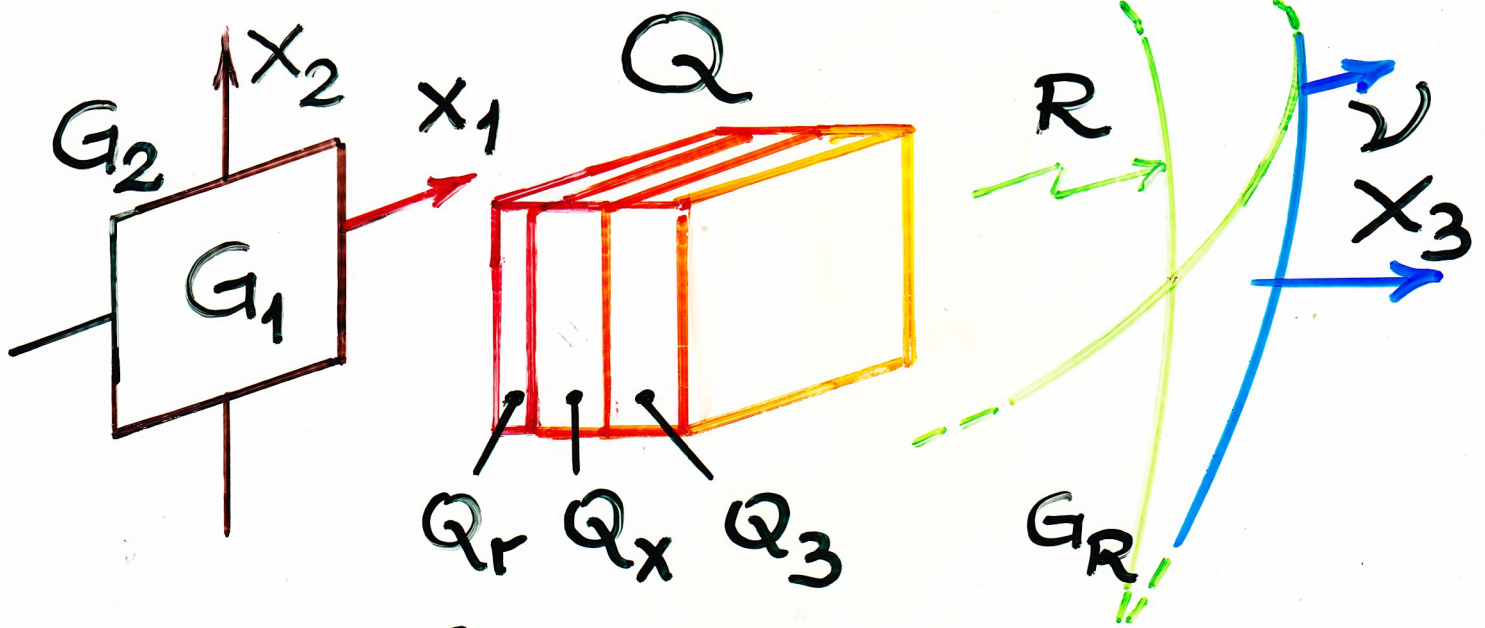
SILIZIUM-
Dünnschichtoptik
SCHEIBE



GESAMTMODELL



PROBLEMGOMETRIE



$$Q := \mathbb{R}_+^3 \setminus Q_3$$

$$\partial Q_R := G_1 \cup G_2 \cup G_3 \cup G_R$$

$$\partial Q := \lim_{R \rightarrow \infty} \partial Q_R$$